

Supplementary information

Induced Spin Polarization in Graphene via Interaction with Halogen Doped MoS₂ and MoSe₂ Monolayers by DFT Calculations

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S11. Calculation details

1.1) Work function calculation

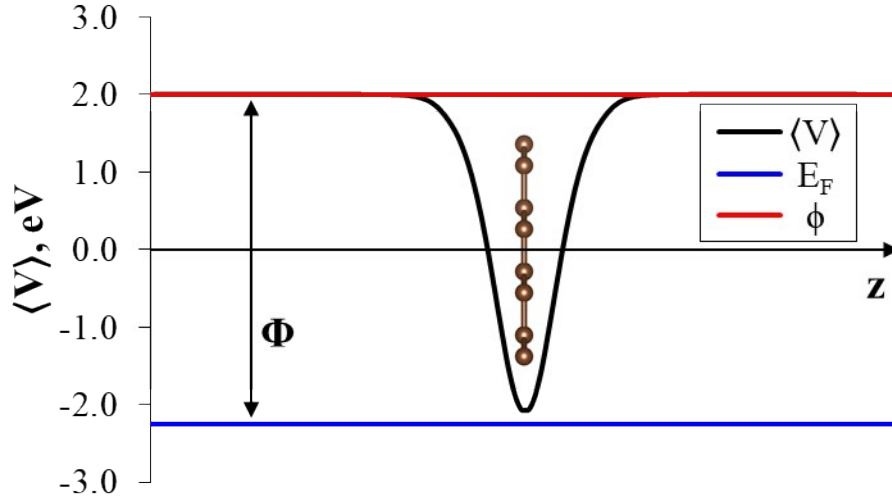


Figure S1. The averaged electrostatic potential $\langle V \rangle$ dependence on the z-direction for pristine graphene.

The work function (Φ) can be calculated as the difference between the vacuum level (ϕ) and the Fermi energy (E_F) of the system. The vacuum level (ϕ) can be found from the electrostatic potential averaged over (xy) plane dependence on the z coordinate. As an example, we presented the calculation of work function for pristine single-layer graphene:

$$\Phi = \phi - E_F = 2.00 - (-2.26) = 4.26 \text{ eV}$$

1.2) Charge density difference (CDD) analysis

In order to estimate the amount of charge transferred from graphene to MoX_2^* ($X = \text{S}, \text{Se}$) layer the charge density difference analysis was carried out. The charge transfer can be determined as follow:

$$\Delta\rho(\vec{r}) = \rho_{\text{Het}}(\vec{r}) - \rho_{\text{MoX}_2^*}(\vec{r}) - \rho_{\text{graphene}}(\vec{r}),$$

where $\rho_{\text{Het}}(\vec{r})$, $\rho_{\text{MoX}_2^*}(\vec{r})$ and $\rho_{\text{graphene}}(\vec{r})$ are total charge densities of considered heterostructure, MoX_2^* and graphene layers, respectively. The total amount of charge transfer can be estimated as:

$$\Delta Q(z) = \int_{-\infty}^z \Delta\rho(z') dz'$$

where $\Delta\rho(z')$ is the plane-averaged $\Delta\rho(\vec{r})$ among the normal direction to the heterostructure basal plane obtained by integration of $\Delta\rho(\vec{r})$ within the x-y plane at z' point. The number of charge transferred from graphene to MoX_2^* ($X = \text{S}, \text{Se}$) layer can be estimated by finding the maximum (minimum) value of $\Delta Q(z)$.

1.3) Lattice mismatch calculation

The lattice mismatch in considered heterostructures was calculated as follow:

$$\alpha = \frac{|a_{\text{graphene}} - a_{\text{MoX}_2}|}{a_{\text{graphene}}} * 100\%$$

where a_{graphene} and a_{MoX_2} are the optimized lengths of graphene and MoX₂ supercells translation vectors, respectively.

The deformation of individual layers in heterostructures was calculated as:

$$\alpha = \frac{|a_{\text{heterostructure}} - a_{\text{free}}|}{a_{\text{free}}} * 100\%$$

where $a_{\text{heterostructure}}$ and a_{free} are the structure translation vectors in heterostructure and individual layer, respectively.

SI2. Halogen-doped MoX₂ (X = S, Se) layers

The optimized lattice parameters of pristine graphene, MoS₂ and MoSe₂ layers are 2.468 Å, 3.164 Å and 3.293 Å, respectively. The obtained values are in a good agreement with experimental measurements^{1,2}.

1) The thermodynamics of defects formation in the MoX₂ structures

Chalcogen monovacancies formation for MoS₂ and MoSe₂ monolayers do not lead to the appearance of magnetic moment³⁻⁸. We used 4x4x1 and 3x3x1 supercells with one chalcogen atom vacancies in the case of MoS₂ and MoSe₂ monolayers, respectively. Such supercell size choice is due to future applications for the construction of heterostructures with graphene.

The monovacancies formation energies were calculated using the following equation:

$$E_f = E[\text{MoX}_2\text{vac}] + E[\text{X}] - E[\text{MoX}_2 \text{ pure}],$$

where $E[\text{MoX}_2\text{vac}]$ is the total energy of the defected MoX₂ layer with X atom vacancy, $E[\text{X}]$ is the chemical potential for X atom, $E[\text{MoX}_2 \text{ pure}]$ is the total energy of the pristine MoX₂ monolayer. The chemical potential of S atom was calculated from the bulk with Fddd space group, the unit cell of the crystal consists of 128 atoms. For Se atom chemical potential calculation a bulk crystal with P3₁21 space group was used.

Calculated values of monovacancies formation energies are presented in Table S1.

Table S1. The chalcogen monovacancy formation energies for the MoX₂ (X = S, Se) structure.

	E _f , eV
S vacancy	2.70
Se vacancy	2.61

Obtained values of monovacancies formation energies are in a good agreement with previously reported values^{4,6,9,10}. The positive value of monovacancies formation indicates that the process is endothermic, and the formation of defective structures is not energetically favorable.

Table S2. The binding energy of halogen atoms with MoX₂ structure

Dopant atom	MoS ₂	MoSe ₂
F	-2.96	-2.86
Cl	-1.51	-1.47
Br	-1.01	-0.96
I	-0.53	-0.47

2) *Magnetic and electronic properties of defective MoX₂ structures*

Table S3. The estimation of the atomic charges on the halogen dopant according to Bader charge analysis

Dopant atom	MoS ₂	MoSe ₂
F	-0.66 e	-0.68 e
Cl	-0.46 e	-0.52 e
Br	-0.33 e	-0.38 e
I	-0.14 e	-0.19 e

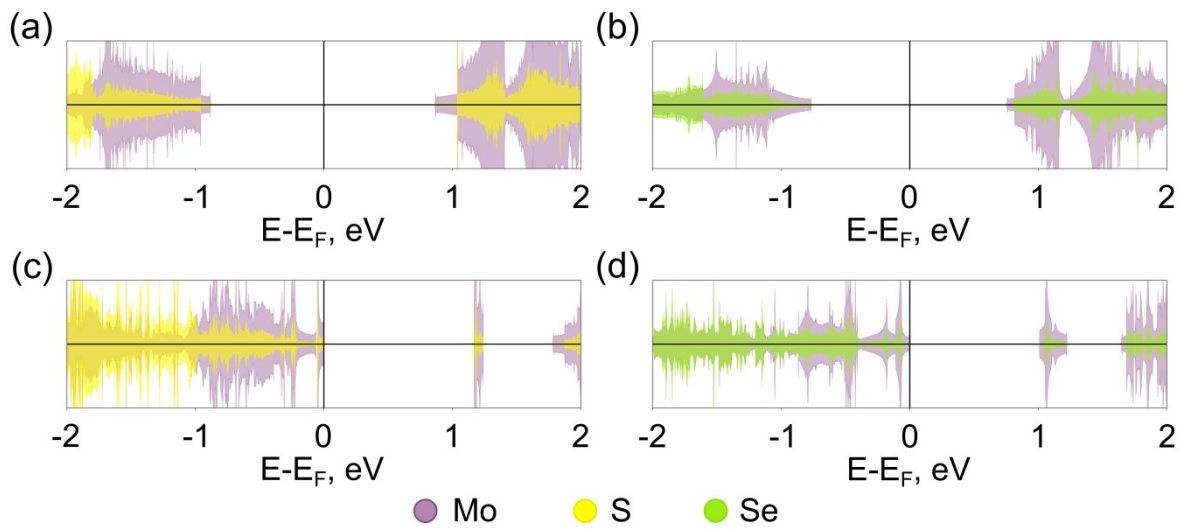


Figure S2. Atom and spin-resolved density of states for MoS₂ (a,c) and MoSe₂ (b,d) layers with perfect structure (a, b) and with monovacancy of chalcogen atom (c, d).

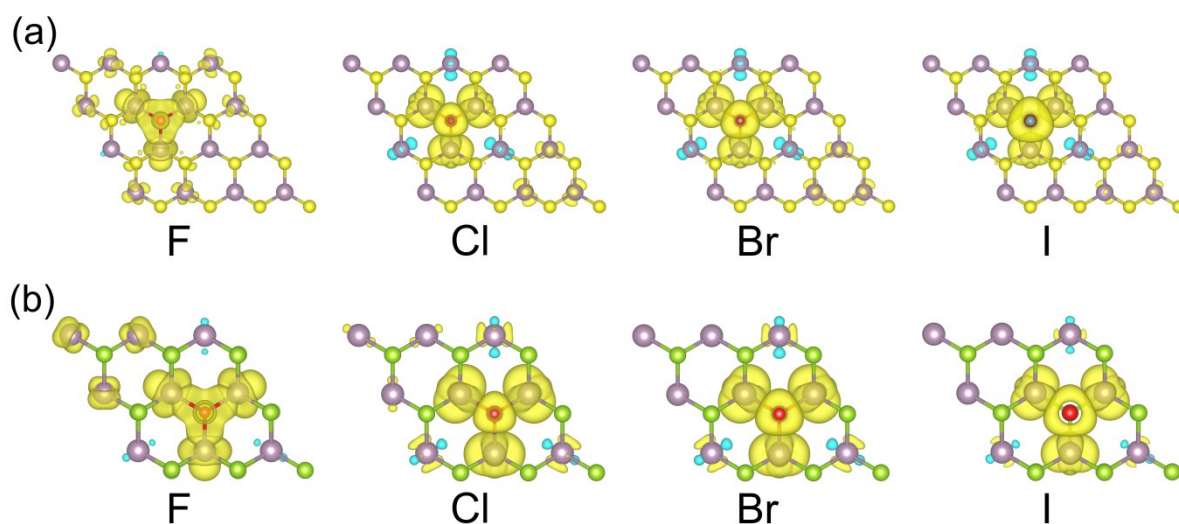


Figure S3. Spin density distribution in (a) MoS₂ and (b) MoSe₂ layers doped by halogen atoms (F, Cl, Br, I). By purple, yellow, green and red colors the Mo, S, Se and halogen atoms are depicted, respectively. By yellow and blue clouds electron distribution (the isosurface level is 10⁻³ e/Å³) with spin up and down is depicted.

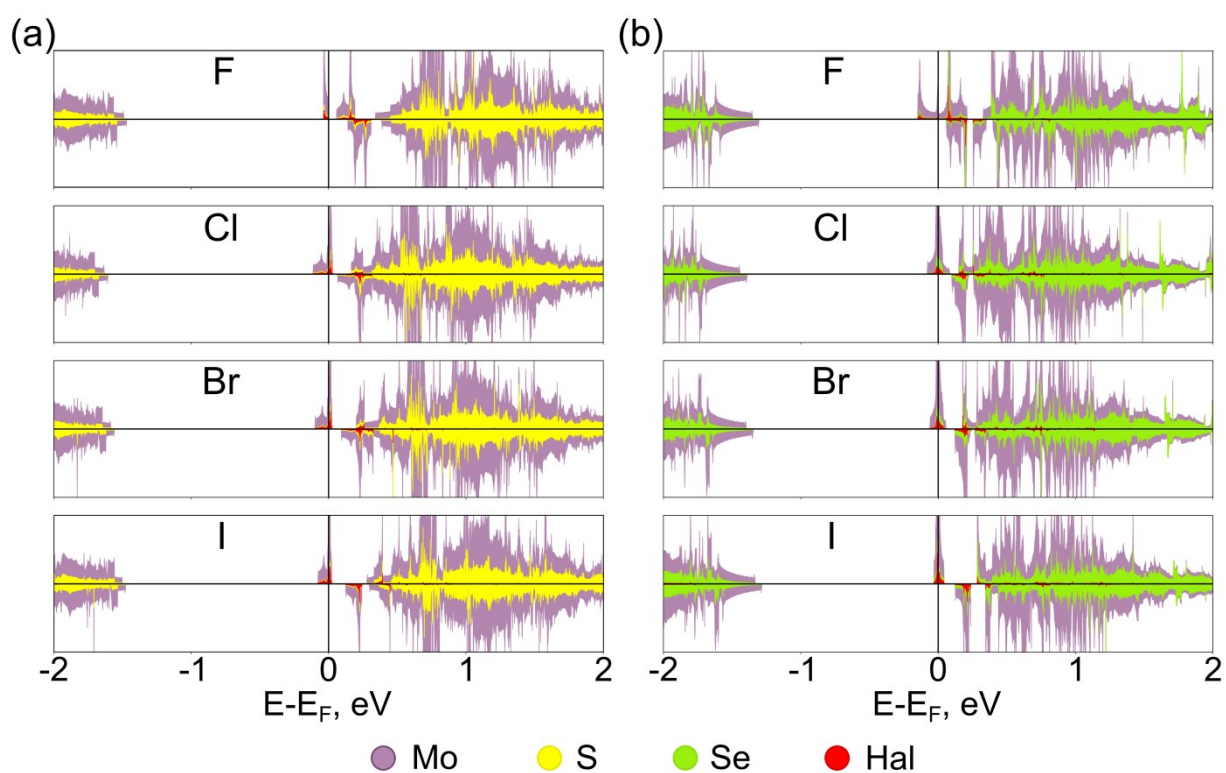


Figure S4. Spin and atom resolved DOS for MoS₂* and MoSe₂*. Purple, yellow, green and red lines corresponds to the electron density from Mo, S, Se and halogen (F, Cl, Br, I) atoms, respectively.

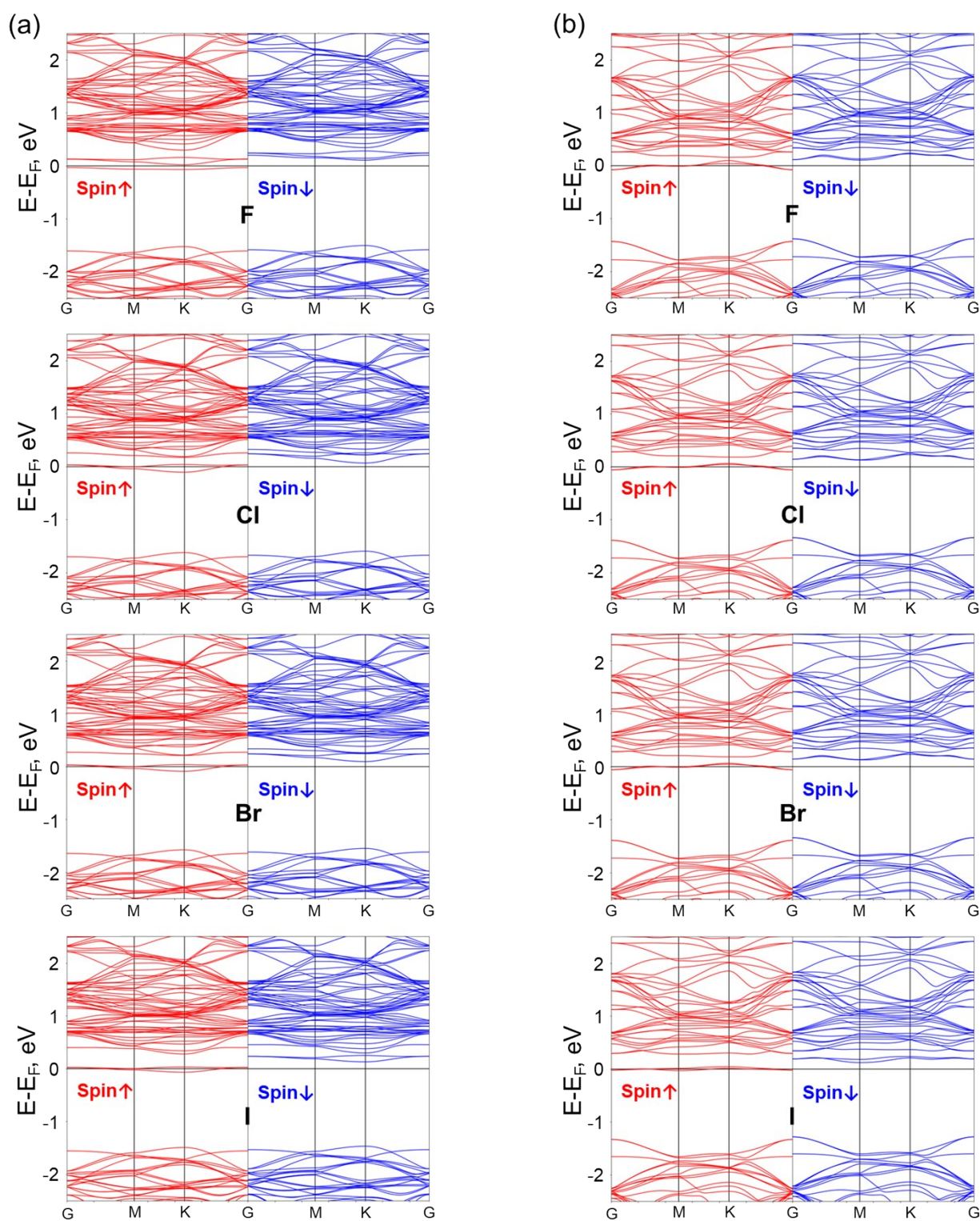


Figure S5. Spin-resolved electronic band structures for halogen doped (a) MoS₂ and (b) MoSe₂ monolayers.

SI3. $\text{MoX}_2^*/\text{graphene}$ heterostructures ($X = \text{S, Se}; * = \emptyset, \text{F, Cl, Br, I}$)

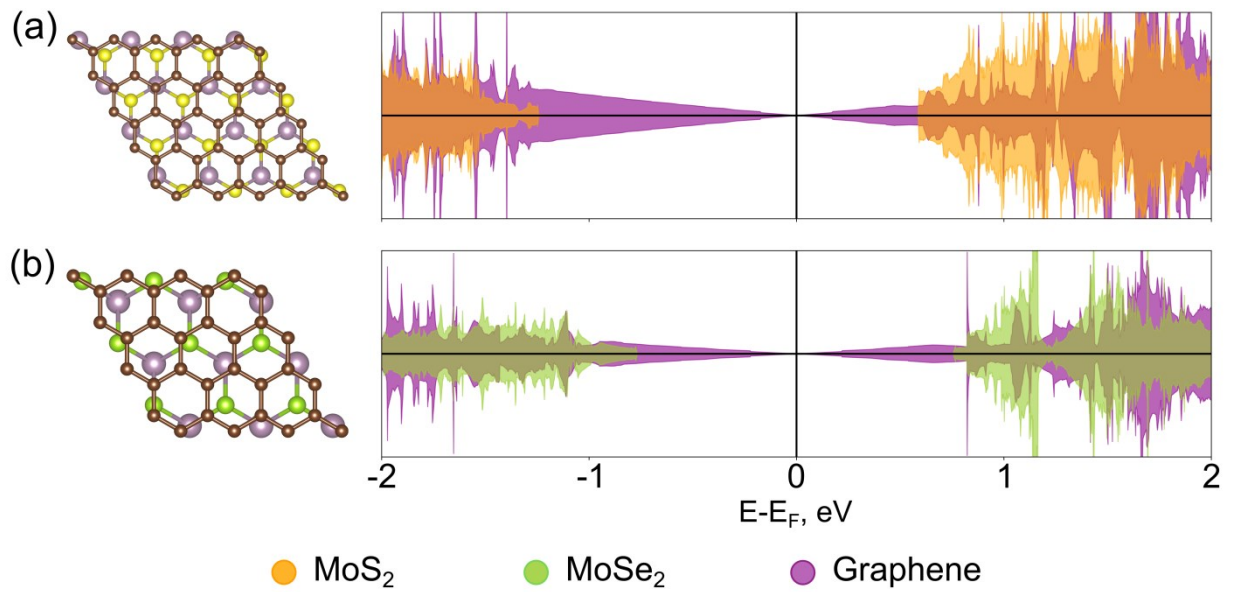


Figure S6. Atom-resolved density of states for pristine (a) $\text{MoS}_2/\text{graphene}$ and (b) $\text{MoSe}_2/\text{graphene}$ heterostructures. Contribution from graphene was enlarged by 10 times for better representation. It is worth mentioning that the Dirac cone is located in the vicinity of Fermi energy.

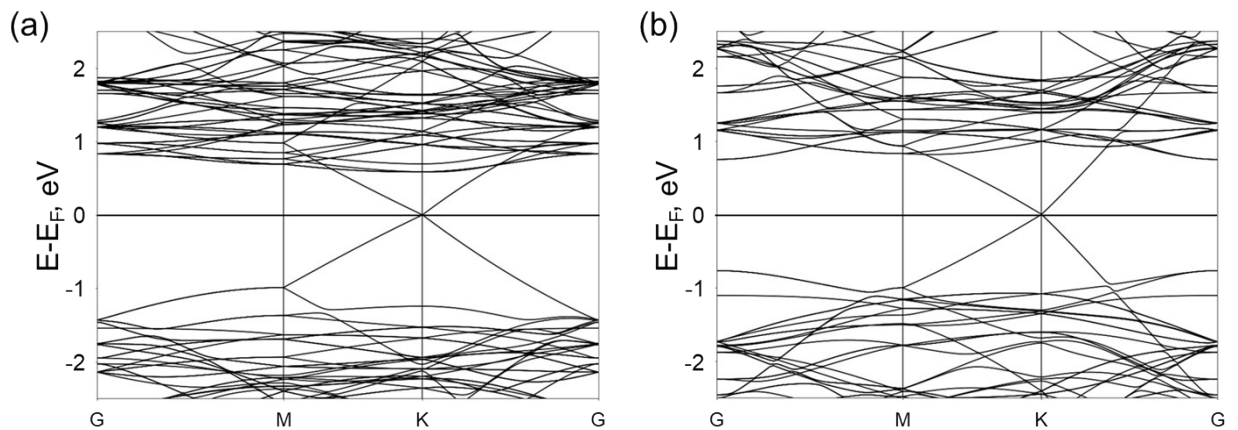


Figure S7. Electronic band structures for (a) $\text{MoS}_2/\text{graphene}$ and (b) $\text{MoSe}_2/\text{graphene}$ heterostructures.

Table S4. Minimum interlayer distances between transition metal dichalcogenide and graphene layers. The distance was found relative to chalcogen atoms and dopant atom.

Heterostructure	Dopant atom	Distance, Å	
		From S(Se) atom	From dopant atom
MoS ₂ /graphene	-	3.40	-
MoS ₂ */graphene	F	3.28	3.50
	Cl	3.34	3.17
	Br	3.41	3.07
	I	3.43	2.92
MoSe ₂ /graphene	-	3.44	-
MoSe ₂ */graphene	F	3.42	3.78
	Cl	3.44	3.52
	Br	3.46	3.36
	I	3.51	3.22

Table S5. Energy shift of the Dirac cone relative to the Fermi energy for the MoS₂*/graphene and MoSe₂*/graphene heterostructures. Positive values correspond to displacement deeper into the valence band, negative values correspond to shift deeper into the conduction band

Dopant atom	Dirac cone shift, eV	
	MoS ₂ */graphene	MoSe ₂ */graphene
F	0.01	-0.02
Cl	-0.19	-0.37
Br	-0.20	-0.37
I	-0.27	-0.38

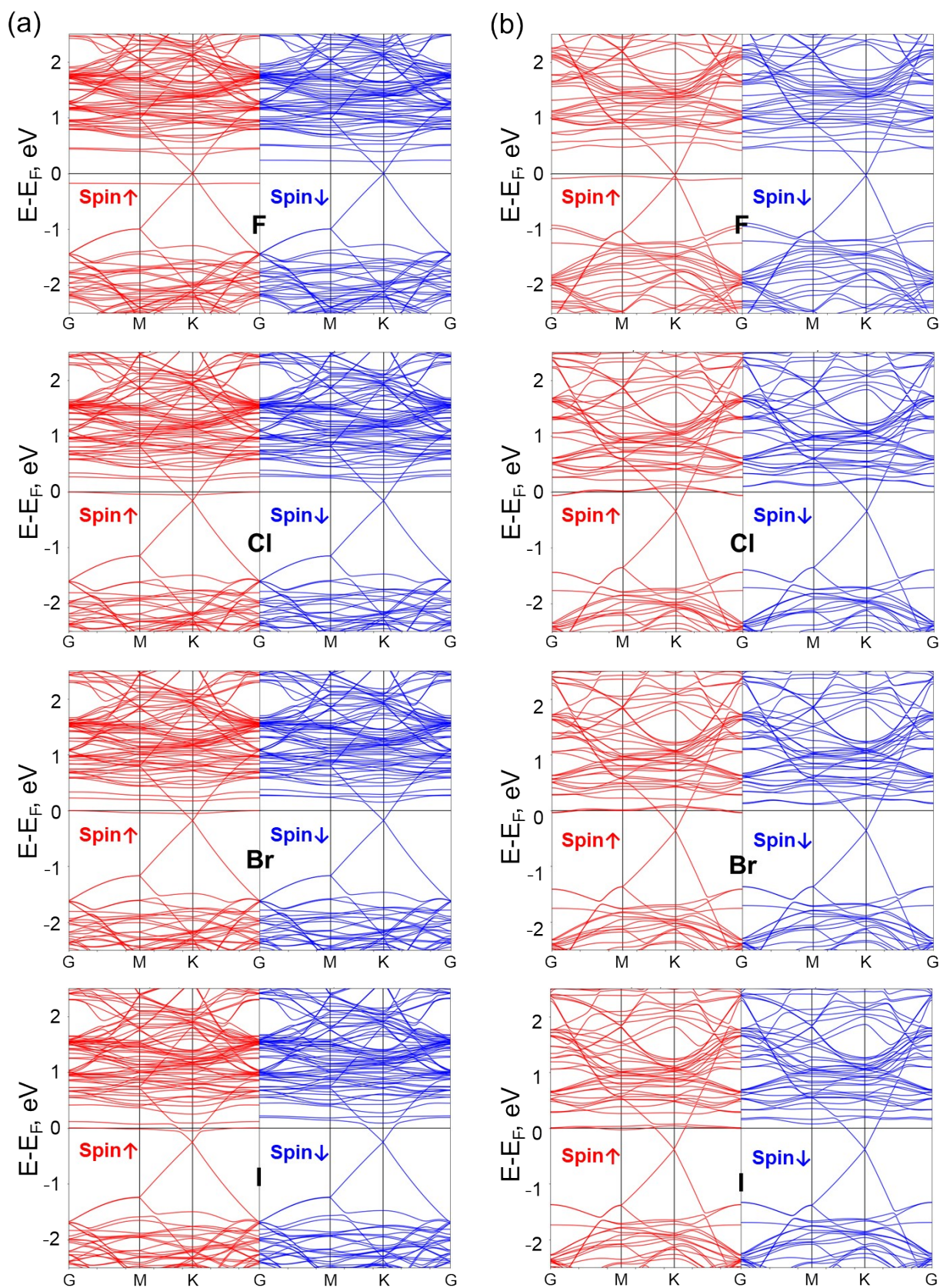


Figure S8. Spin-resolved electronic band structures for (a) MoS₂*/graphene and (b) MoSe₂*/graphene heterostructures.

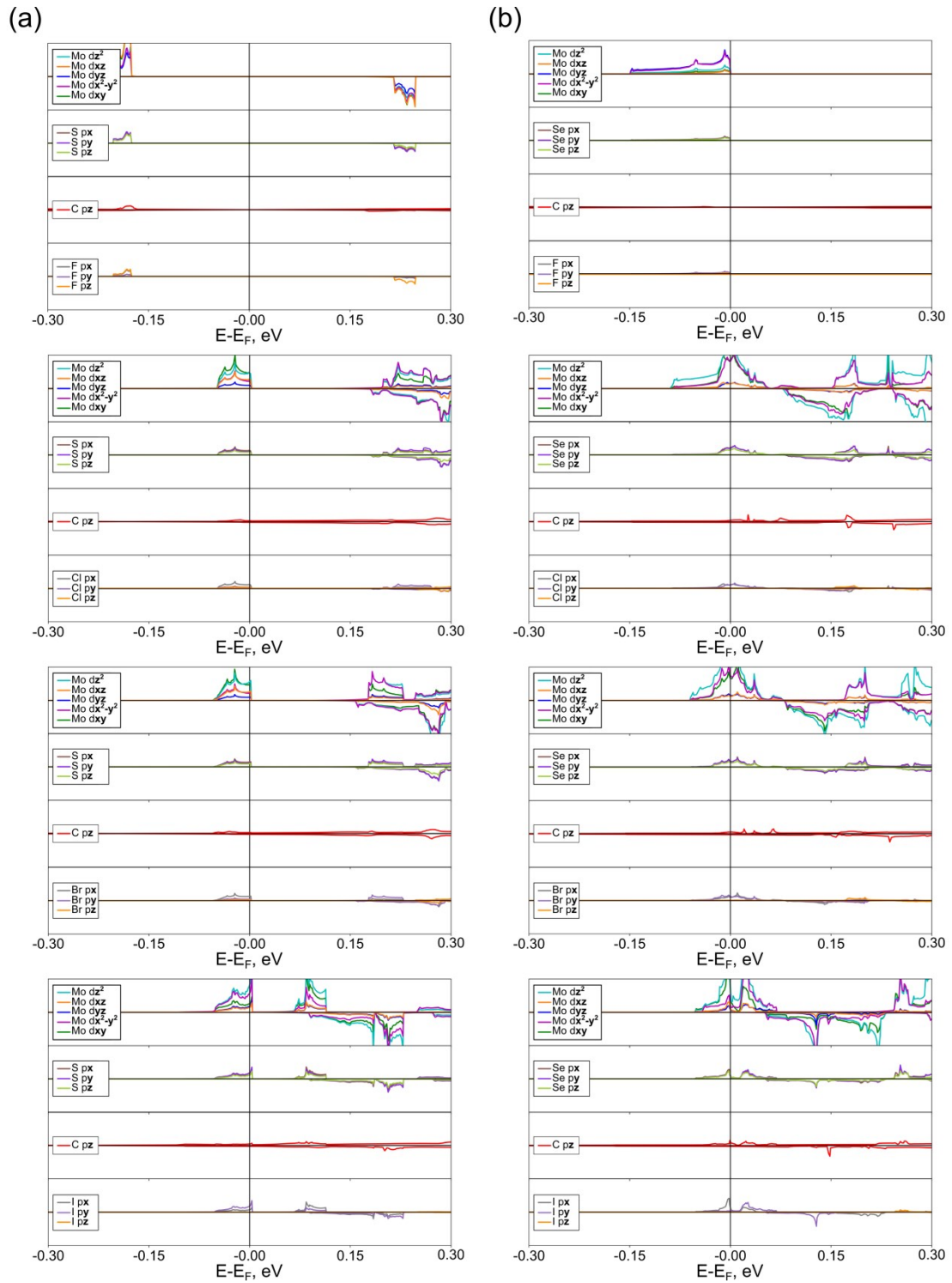


Figure S9. Orbital-resolved density of states for (a) MoS₂*/graphene and (b) MoSe₂*/graphene heterostructures.

Table S6. The number of electrons transferred from graphene to MX_2 layer per one carbon atom. Bader charge analysis and Charge density difference (CDD) analysis.

Dopant atom	$N_e, 10^{-4}$ per C atom			
	$\text{MoS}_2^*/\text{graphene}$		$\text{MoSe}_2^*/\text{graphene}$	
	Bader	CDD	Bader	CDD
-	8.07	20.70	-4.09	21.48
F	8.97	20.74	-3.09	19.14
Cl	0.76	13.16	-34.82	-8.85
Br	-2.25	10.70	-38.21	-10.53
I	-11.35	7.24	-43.00	-12.54

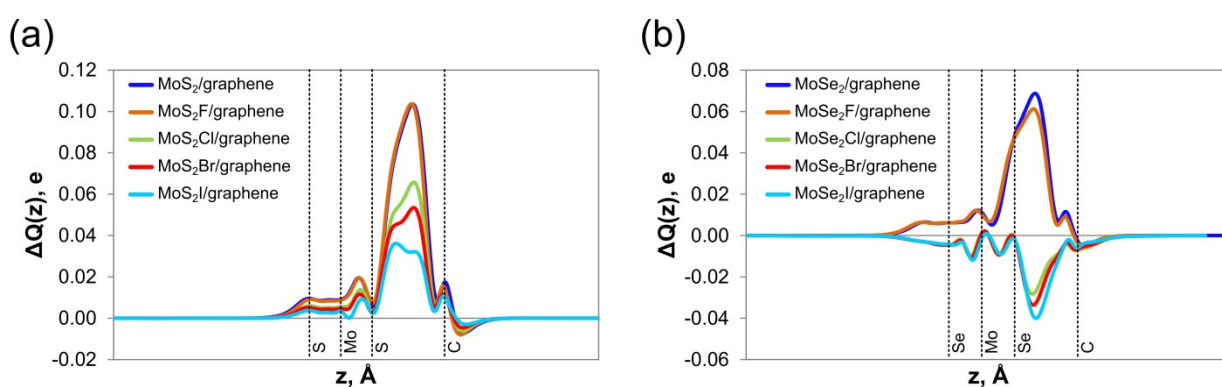


Figure S10. The amount of charge transferred from graphene to MoX_2^* ($X = \text{S}, \text{Se}$) layer along the normal direction $\Delta Q(z)$ estimated by charge density difference analysis.

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